

Thank you for the review of JMADE-D-22-01041

Von: Materials & Design (em@editorialmanager.com)

An: pesitrama_80@yahoo.com

Datum: Samstag, 21. Mai 2022, 01:40 GMT-5

Ms. Ref. No.: JMADE-D-22-01041

Title: Versatile Approach of Silicon Nanofabrication without Resists: Helium Ion-Assisted Chemical Etching (HiaEtch)
Materials & Design

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Yours sincerely,

Eric Le Bourhis
Editors
Materials & Design

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